

Corrections to "A Novel Dual-Directional SCR Structure With High Holding Voltage for 12-V Applications in $0.13-\mu m$ BCD Process"

Kyoung-II Do[®], Graduate Student Member, IEEE, Bo-Bae Song, and Yong-Seo Koo, Member, IEEE

In Section I of the above article [1], the sentence beginning in the 18th line of the second column contains typos that misrepresent the range of voltages. The correct sentence is the following: "However, the strong snapback characteristics of a traditional SCR structure that are caused by high avalanche breakdown between the well regions allow it to have a substantially high trigger voltage (approximately 17–22 V) and low holding voltage (approximately 2–4 V)."

REFERENCES

[1] K.-I. Do, B.-B. Song, and Y.-S. Koo, "A novel dual-directional SCR structure with high holding voltage for 12-V applications in 0.13-μm BCD process," *IEEE Trans. Electron Devices*, vol. 67, no. 11, pp. 5020–5027, Nov. 2020.

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Kyoung-II Do and Yong-Seo Koo are with the Department of Electronics and Electrical Engineering, Dankook University, Yongin 16890, South Korea (e-mail: yskoo@dankook.ac.kr).

Bo-Bae Song is with the SoC Platform Research Center, Korea Electronics Technology Institute (KETI), Seongnam 13509, South Korea.

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